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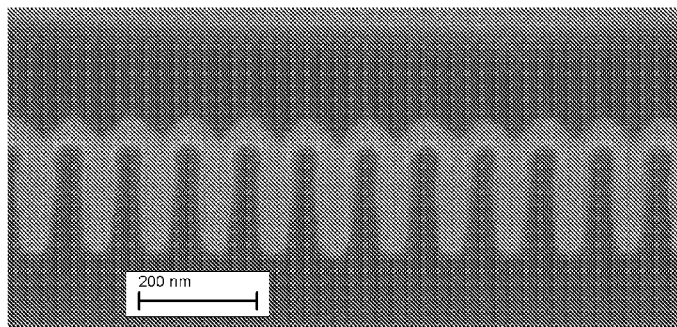
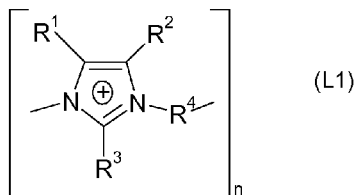
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[Continued on next page]

(54) Title: COMPOSITION FOR METAL ELECTROPLATING COMPRISING LEVELING AGENT

Fig. 3b

(57) Abstract: A composition comprising a source of metal ions and at least one leveling agent comprising a linear or branched, polymeric imidazolium compound comprising the structural unit of formula L1 (L1) wherein R¹, R², R³ are each independently selected from an H atom and an organic radical having from 1 to 20 carbon atoms, R⁴ is a divalent, trivalent or multivalent organic radical which does not comprise a hydroxyl group in the α or β position relative to the nitrogen atom of the imidazole rings, is an integer.



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